



1756 *[Signature]*
Atty. Dkt. No. 039153-0381

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Ramkumar SUBRAMANIAN, et al.

Title: TWO MASK PHOTORESIST
EXPOSURE PATTERN FOR
DENSE AND ISOLATED REGIONS

Appl. No.: 09/887,035

Filing Date: 06/25/2001

Examiner: K. Sagar

Art Unit: 1756

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AMENDMENT TRANSMITTAL

Commissioner for Patents
Washington, D.C. 20231

Sir:

Transmitted herewith is an amendment in the above-identified application.

- ☐ Small Entity status under 37 C.F.R. § 1.9 and § 1.27 has been established by a Small Entity statement previously submitted.
- ☐ Small Entity statement is enclosed.
- ☒ The fee required for additional claims is calculated below:

	Claims as Amended	Previously Paid For	Extra Claims Present	Rate	Additional Claims Fee
Total Claims:	38	32	6	x \$18.00	= \$108.00
Independents:	4	3	1	x \$84.00	= \$84.00
First presentation of any Multiple Dependent Claims:				+ \$280.00	= \$0.00
CLAIMS FEE TOTAL:					= \$192.00

- ☐ Applicant hereby petitions for an extension of time under 37 C.F.R. § 1.136(a) for the total number of months checked below:

<input type="checkbox"/>	Extension for response filed within the first month:	\$110.00	\$0.00
<input type="checkbox"/>	Extension for response filed within the second month:	\$410.00	\$0.00
<input type="checkbox"/>	Extension for response filed within the third month:	\$930.00	\$0.00
<input type="checkbox"/>	Extension for response filed within the fourth month:	\$1,450.00	\$0.00
<input type="checkbox"/>	Extension for response filed within the fifth month:	\$1,970.00	\$0.00
EXTENSION FEE TOTAL:			\$0.00
CLAIMS AND EXTENSION FEE TOTAL:			\$192.00
<input type="checkbox"/>	Small Entity Fees Apply (subtract ½ of above):		\$0.00
TOTAL FEE:			\$192.00

☐ Please charge Deposit Account No. 19-0741 in the amount of \$192.00. A duplicate copy of this transmittal is enclosed.

☒ A check in the amount of \$192.00 is enclosed.

☒ The Commissioner is hereby authorized to charge any additional fees which may be required regarding this application under 37 C.F.R. §§ 1.16-1.17, or credit any overpayment, to Deposit Account No. 19-0741. Should no proper payment be enclosed herewith, as by a check being in the wrong amount, unsigned, post-dated, otherwise improper or informal or even entirely missing, the Commissioner is authorized to charge the unpaid amount to Deposit Account No. 19-0741. If any extensions of time are needed for timely acceptance of papers submitted herewith, applicant hereby petitions for such extension under 37 C.F.R. §1.136 and authorizes payment of any such extensions fees to Deposit Account No. 19-0741.

Please direct all correspondence to the undersigned attorney or agent at the address indicated below.

Respectfully submitted,

Date

3/18/03

By

Leon Radomsky

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22428

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Registration No. 43,445



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Commissioner for Patents
Washington, D.C. 20231

Sir:

This communication is responsive to the Office Action dated December 18, 2002, concerning the above-referenced patent application.

Please amend the application as follows:

In the Claims:

In accordance with 37 CFR § 1.121, please substitute for original claims 2-5, 15, 16, 29, 30, the following rewritten versions of the same claims, as amended. The changes are shown explicitly in the attached "Marked Up Version Showing Changes Made."

2. (Amended) The method of claim 1, wherein patterning the photoresist layer comprises removing the exposed dense and isolated regions in the photoresist layer.

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01 FC:1202
02 FC:1201

108.00 OP
84.00 OP

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